

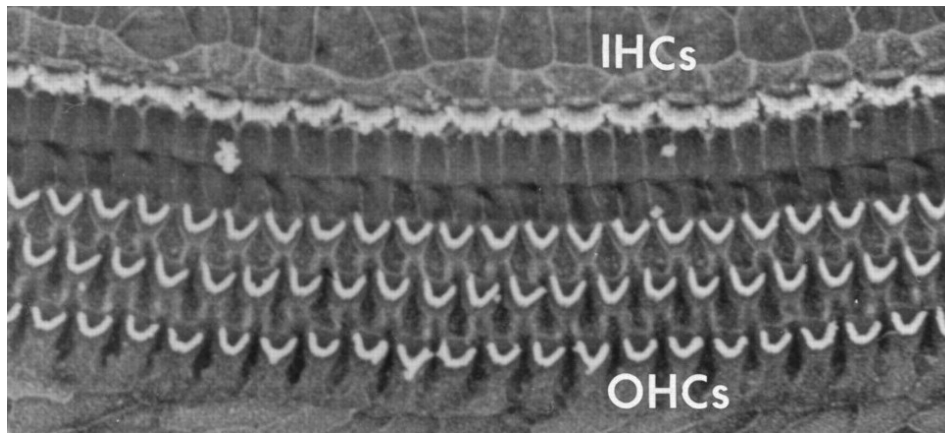
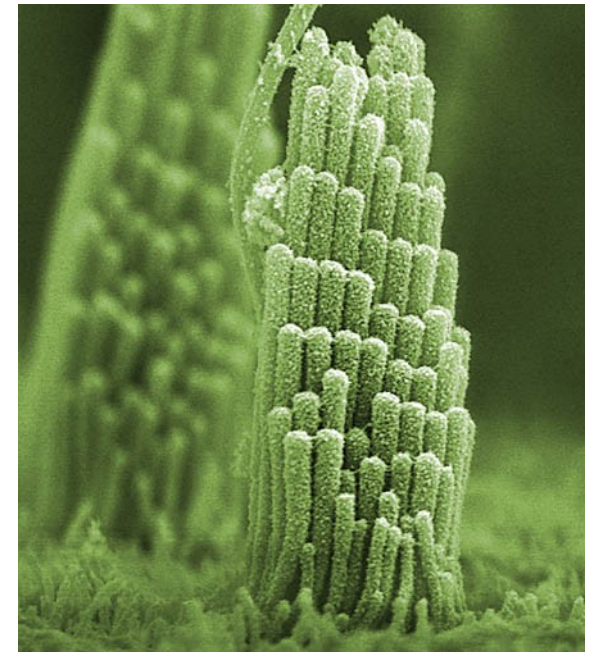
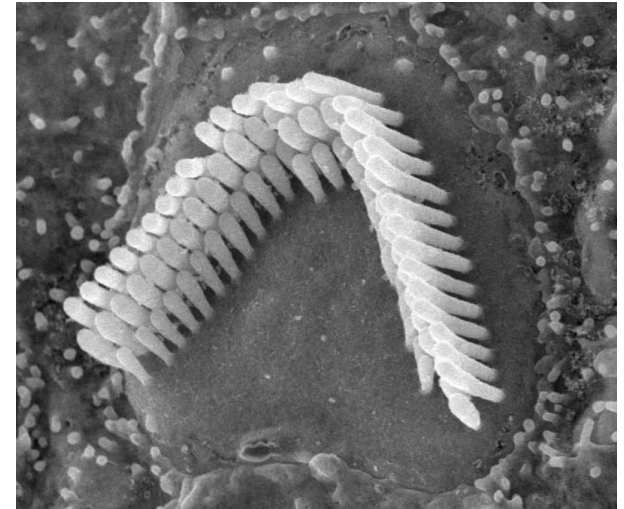
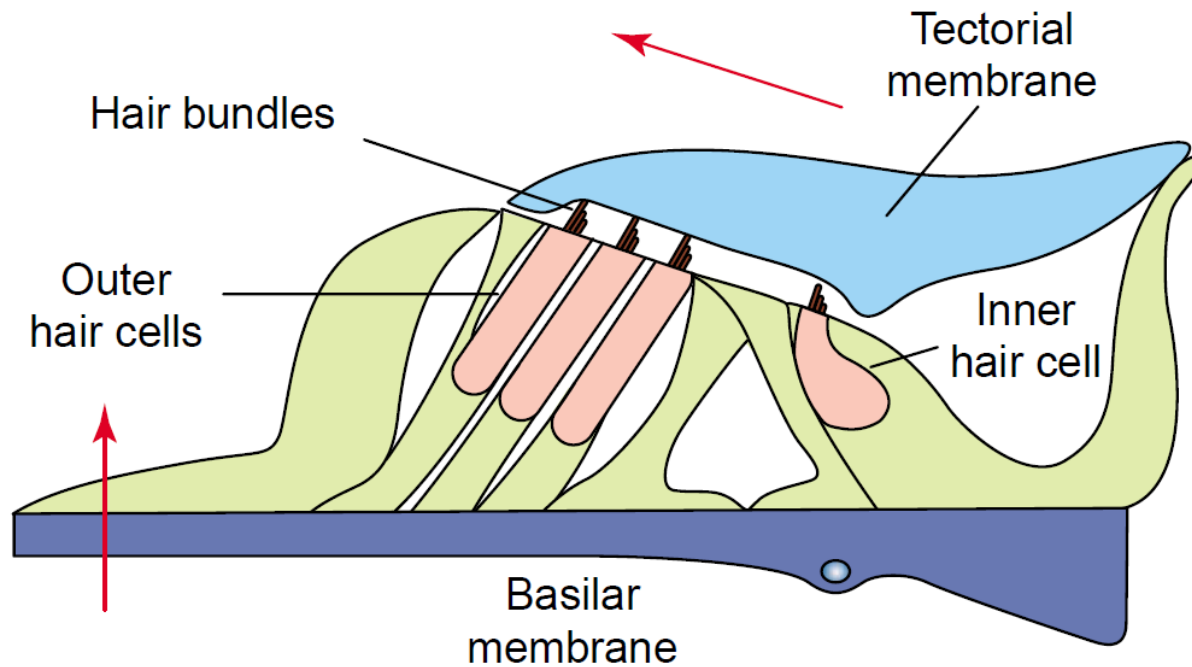
Worm Club Research Update

**Joey Doll
May 9, 2011**

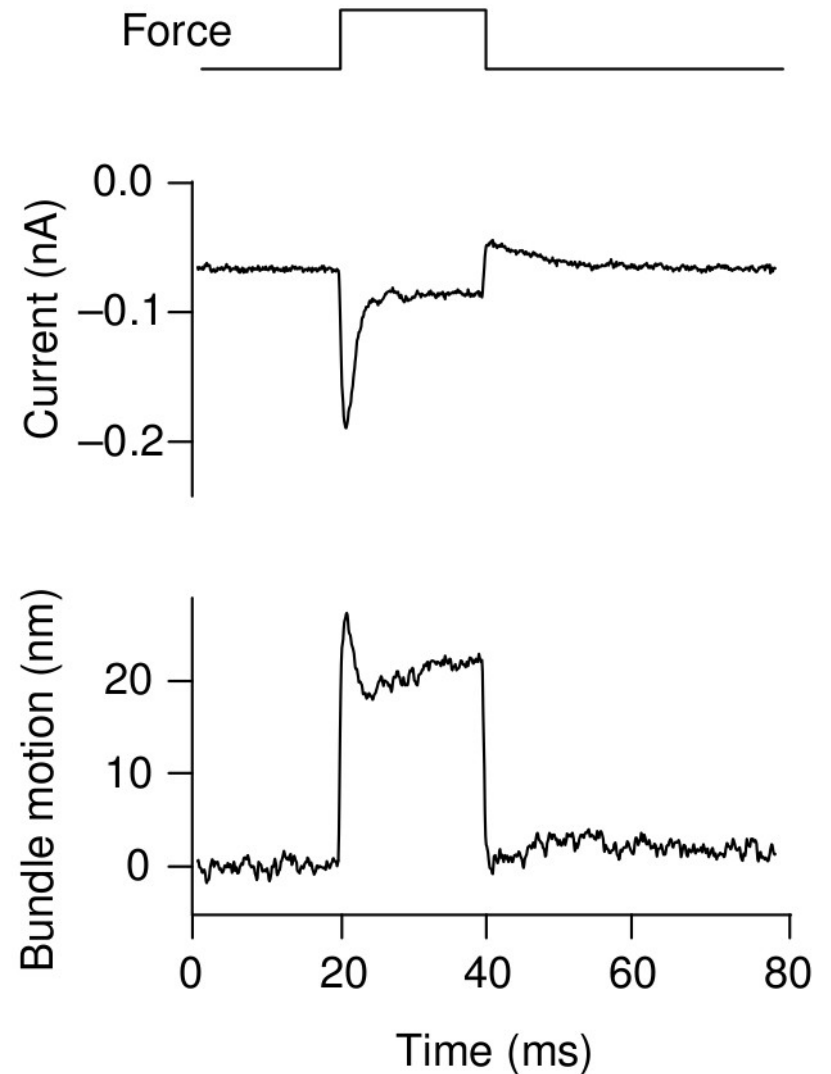
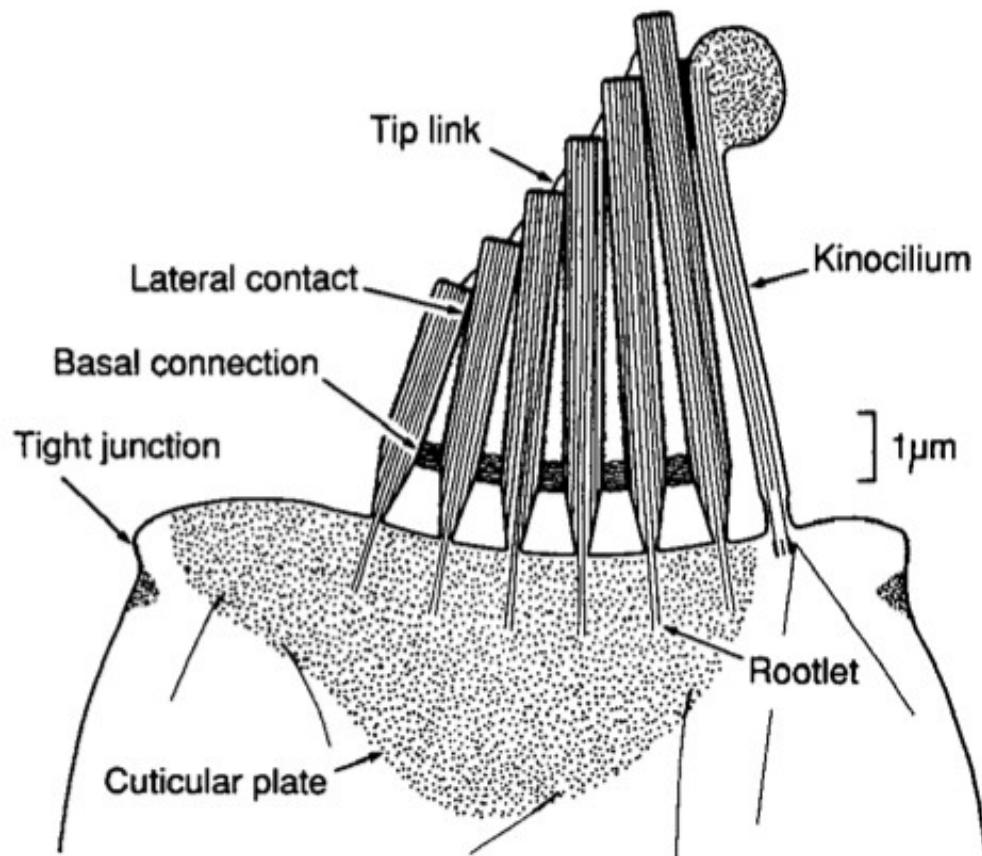
Today

- Motivation and recap
- Progress update
- Debugging and fabrication tricks

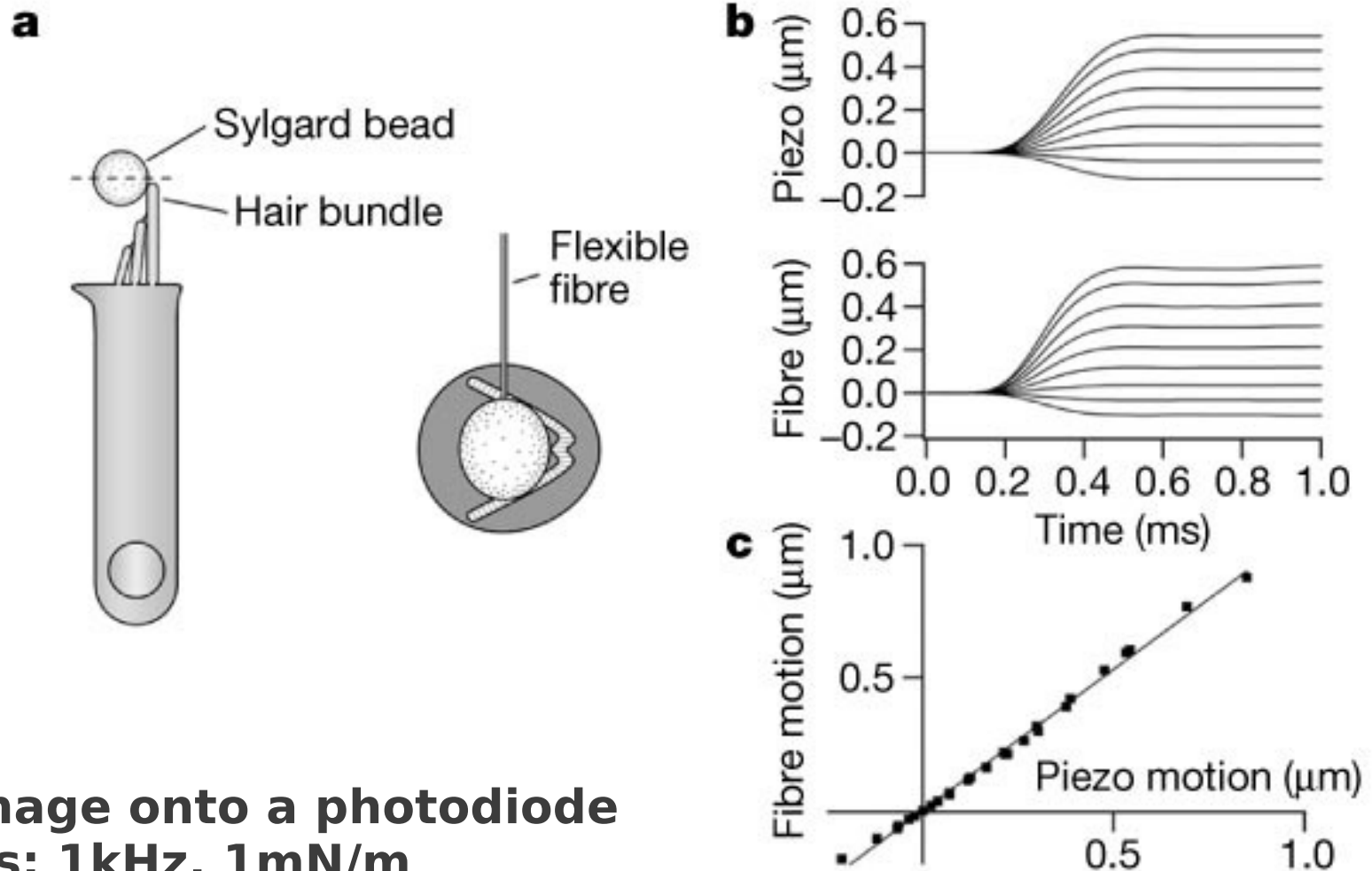
Structure of the Cochlea



The Cochlear Hair Cell



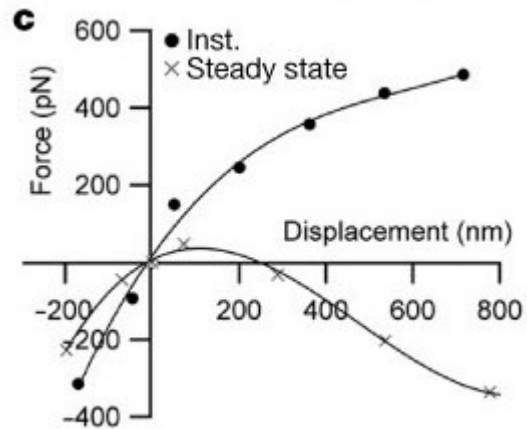
Current Experimental Methods



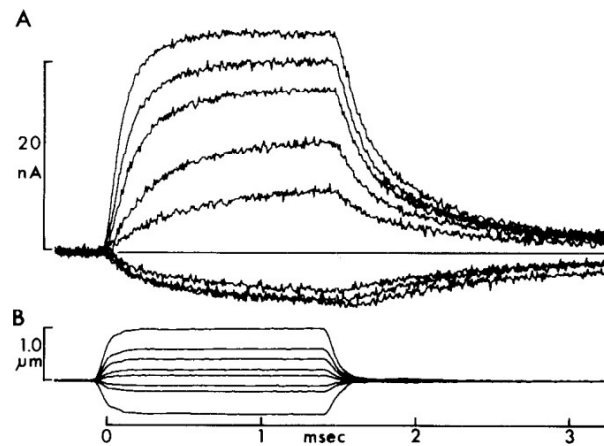
Project image onto a photodiode
Mechanics: 1kHz, 1mN/m
Kinetics: 5-10kHz, >50 mN/m

Cell Experiments

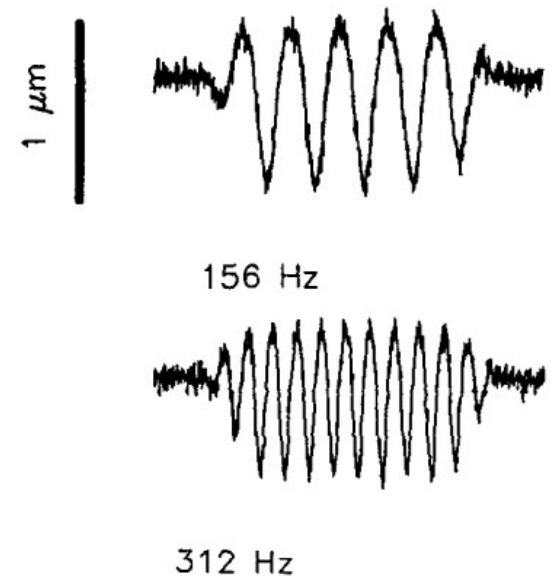
Mechanics



Kinetics



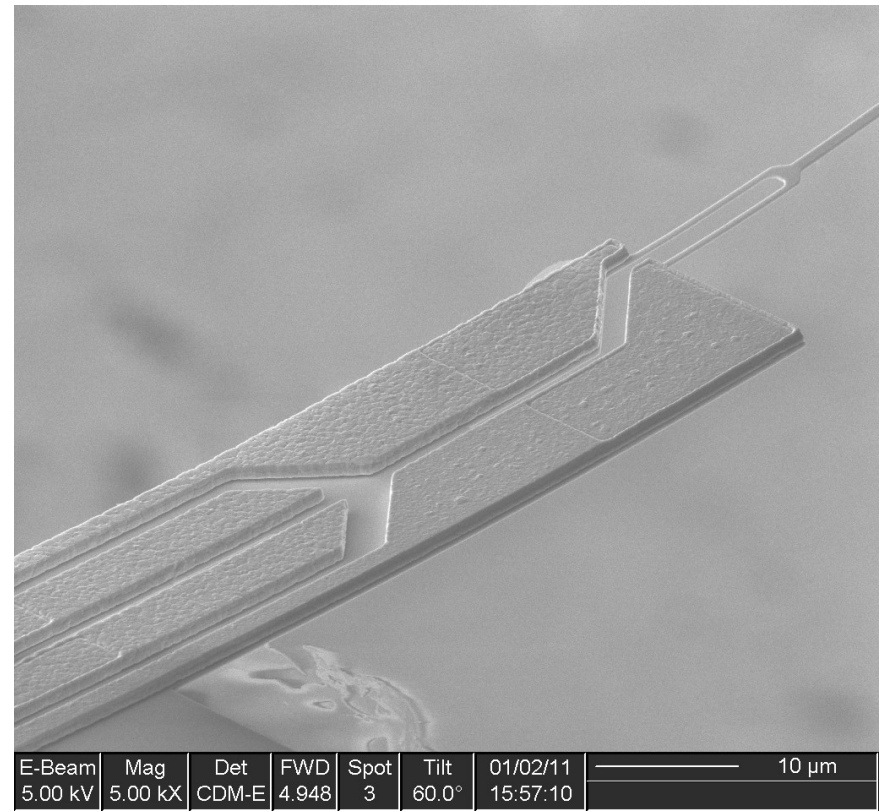
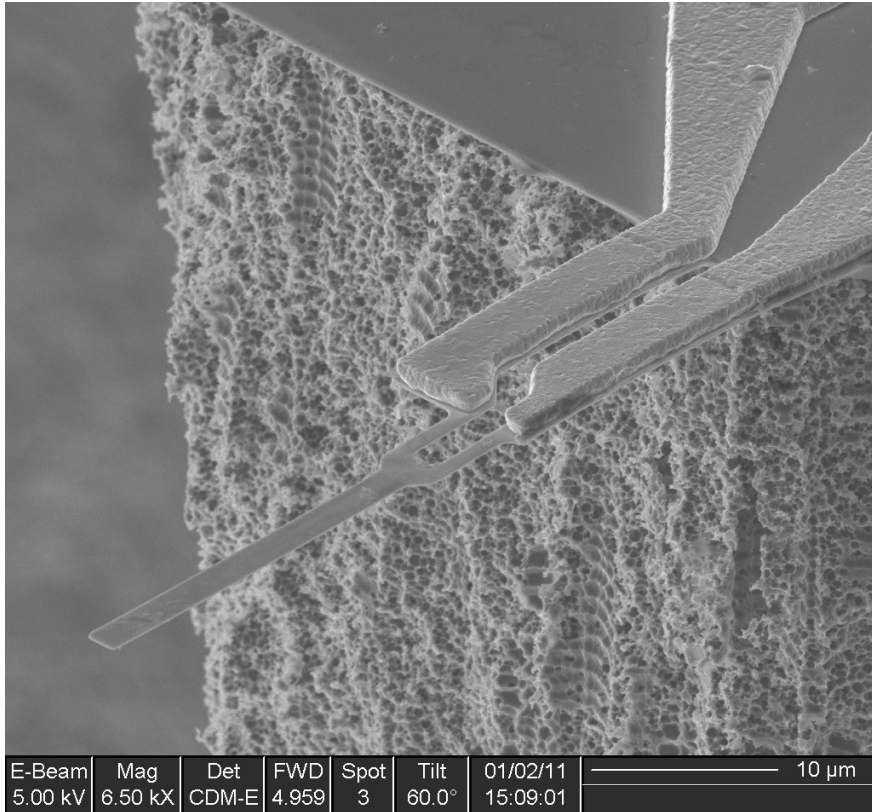
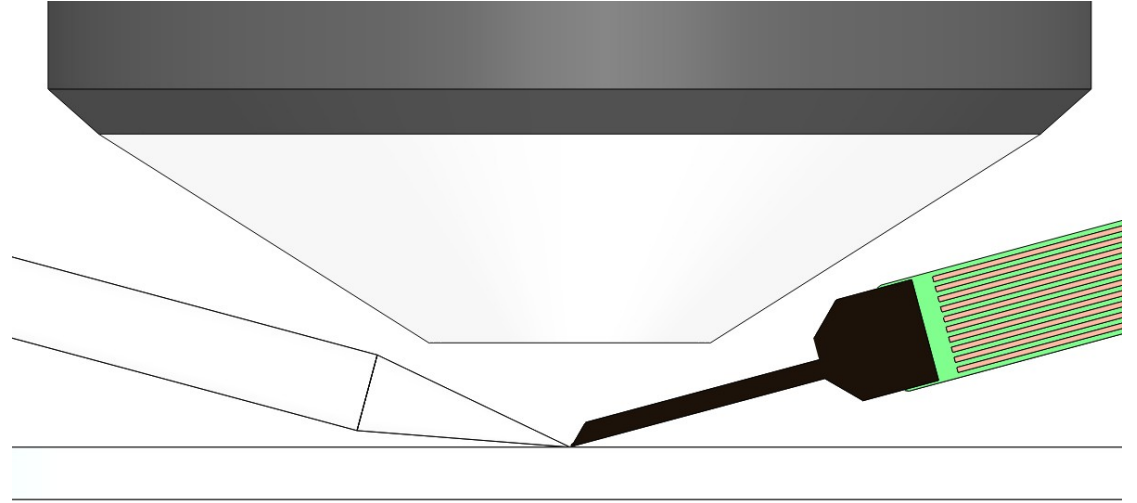
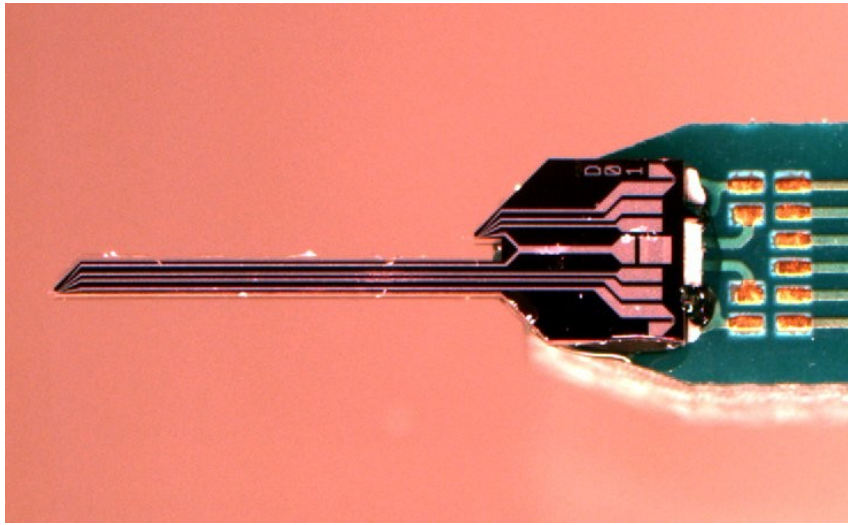
Somatic Motility



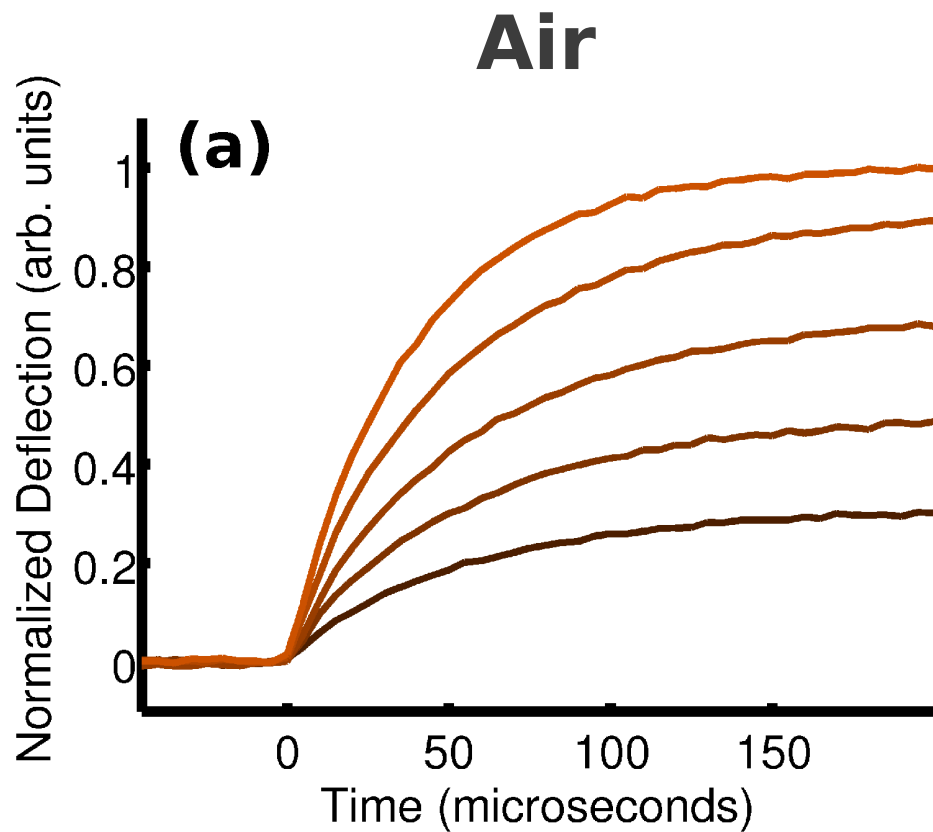
+ touch receptor neurons and other cells/molecules eventually

Device Designs

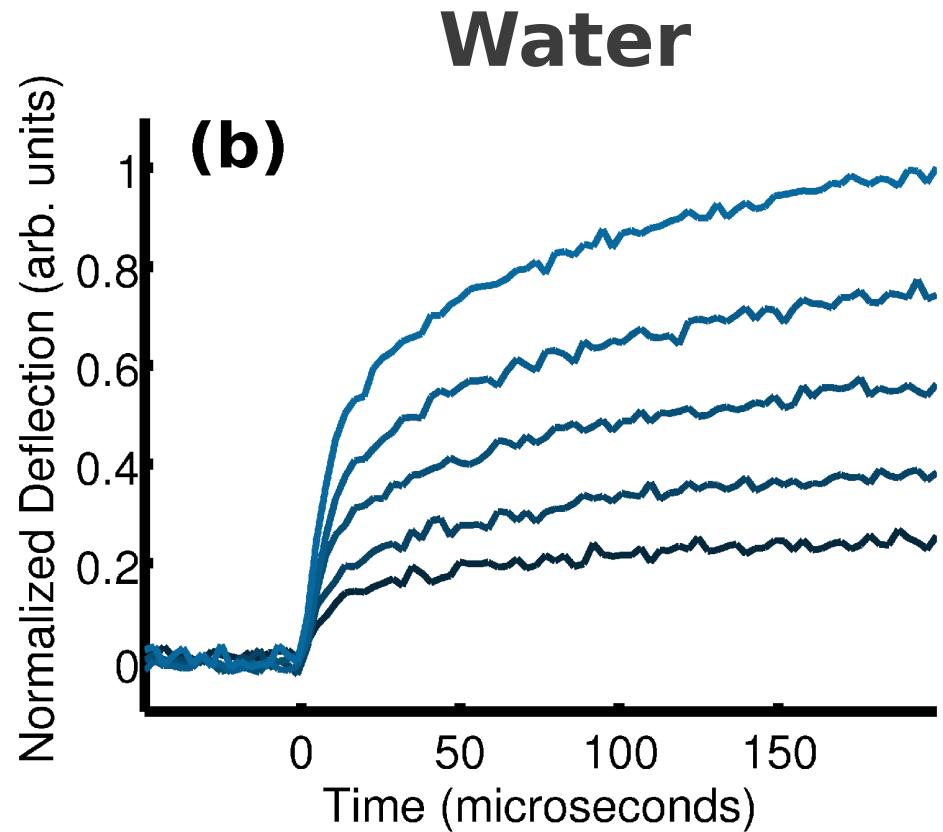
- Mechanics / Motility
 - 0.3 – 4 mN/m
 - 2 – 20 kHz in water (20 – 100 kHz in air)
 - 3 – 30 pN RMS force noise
- Kinetics
 - 10 – 50 mN/m
 - 60 – 200 kHz in water (200 – 500 kHz in air)
 - 30 – 80 pN RMS force noise
- Both types
 - 300 nm thick, 1-2 μm wide, 30-200 μm long
 - On-chip actuation (thermal and piezoelectric)



Thermal Actuator Step Response



$\tau = 57 \pm 10$ microseconds

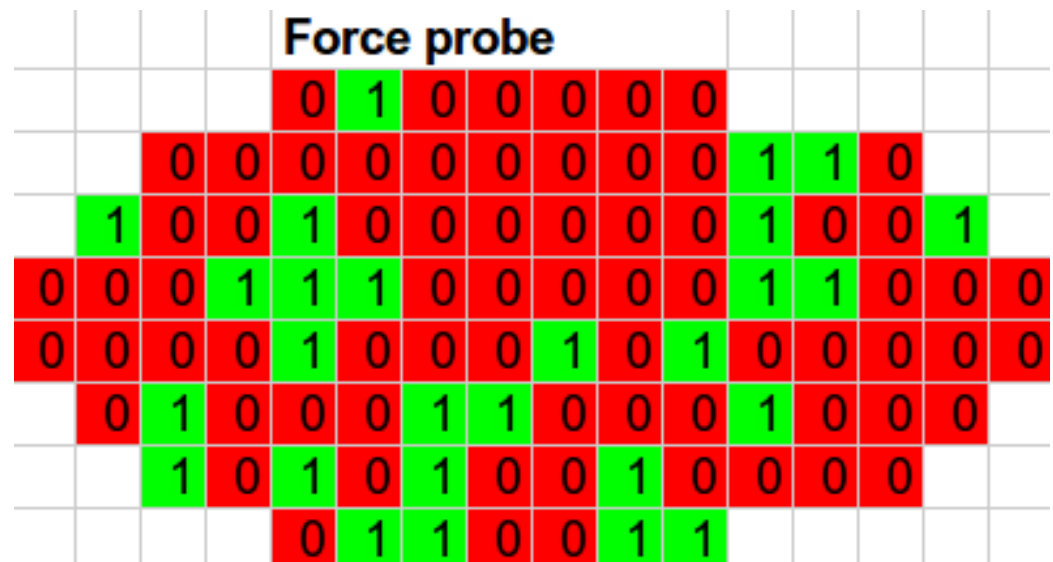


$\tau_1 = 7.9 \pm 1.2$ microseconds
 $\tau_2 = 96 \pm 11$ microseconds

- 1) Measured using a 50kHz split photodiode detector with Anton, Tony and Robert Fettiplace
- 2) Anton is building a faster 500kHz photodiode detector
- 3) Time response limited by heater time constant – piezoelectric will be faster

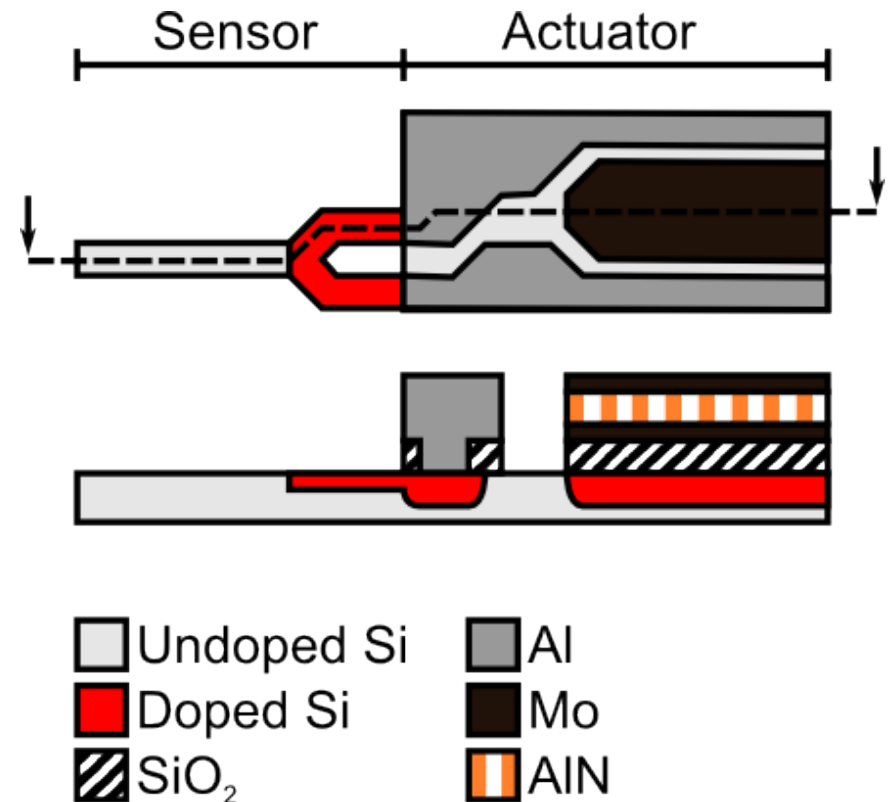
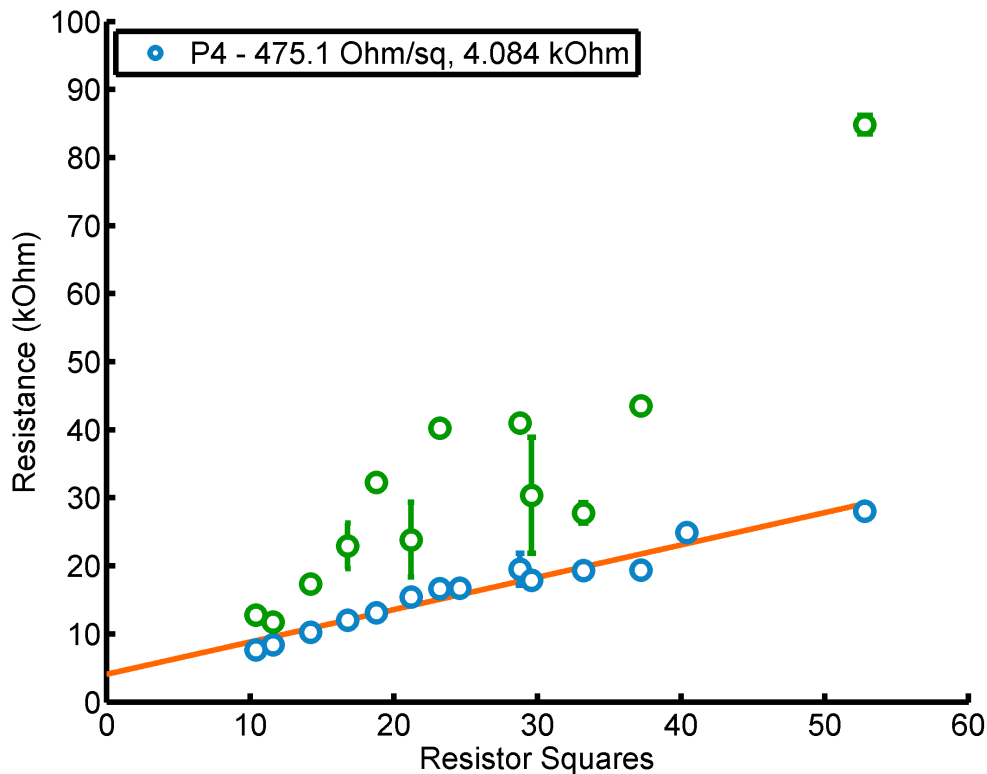
Debugging a Cantilever Process

- Shallow doping and surface damage
- Cracking and low yield
- Polymer goop
- Passivation

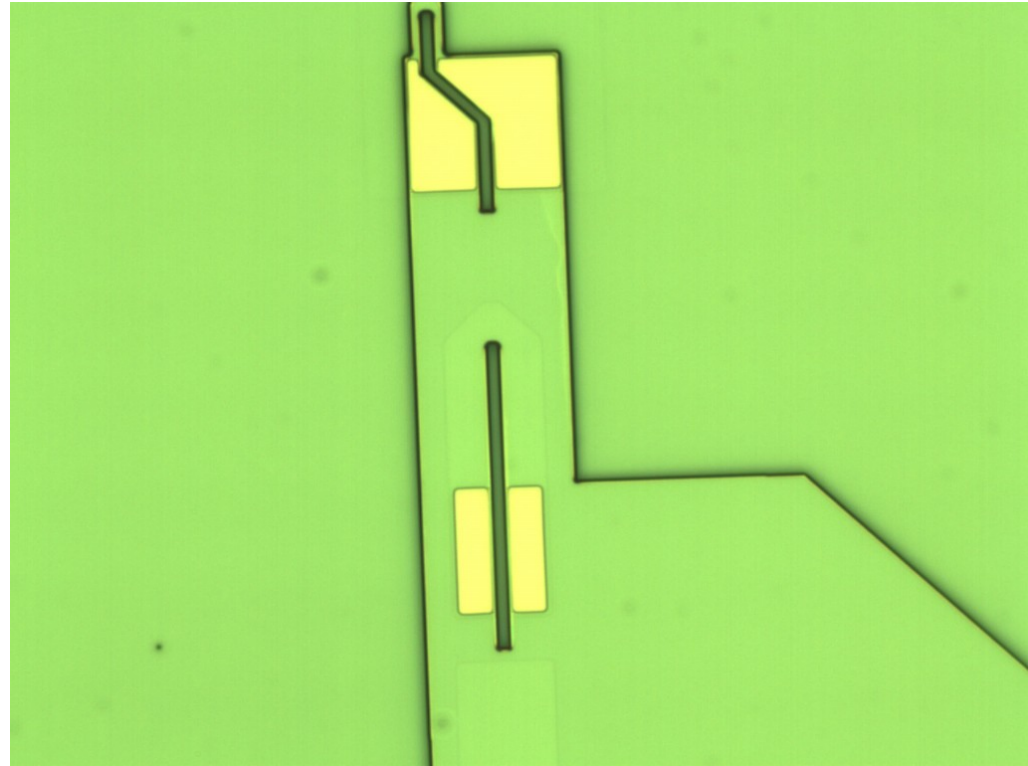
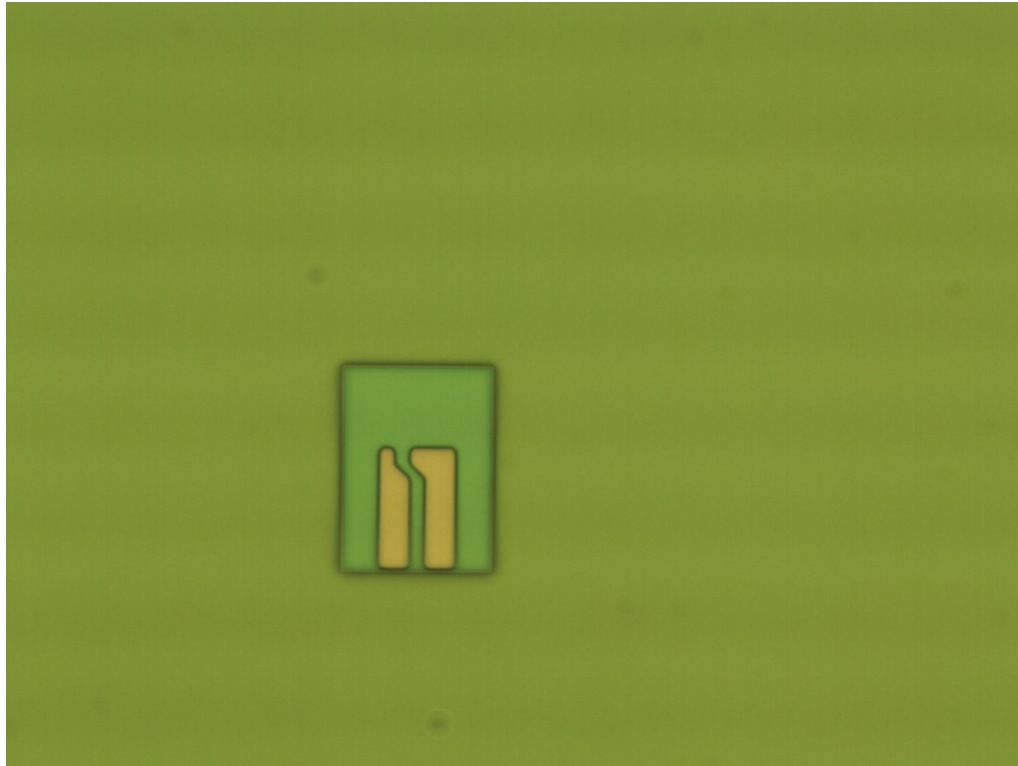


Shallow Doping and Surface Damage

- 1) Increased piezoresistor depth (15nm → 50nm)
- 2) Added an extra contact doping step (150nm deep)
- 3) New tool for release: plasma → HF vapor

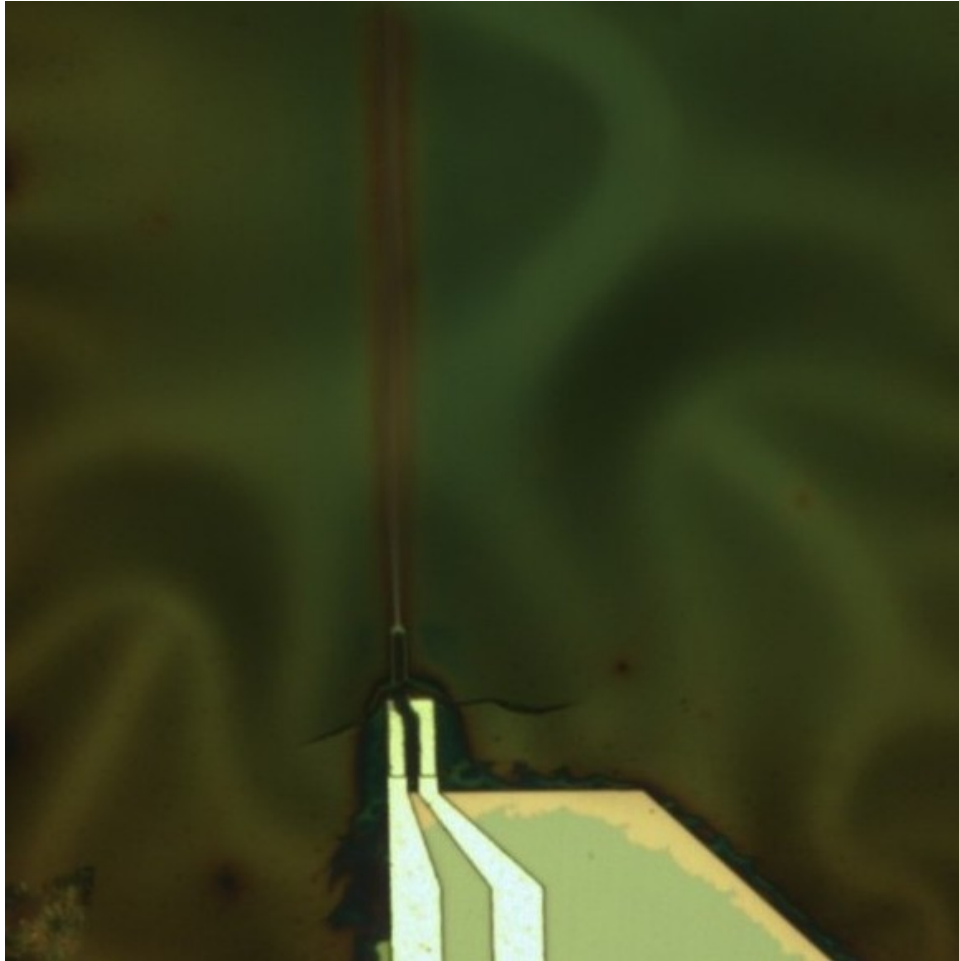


Shallow Doping and Surface Damage

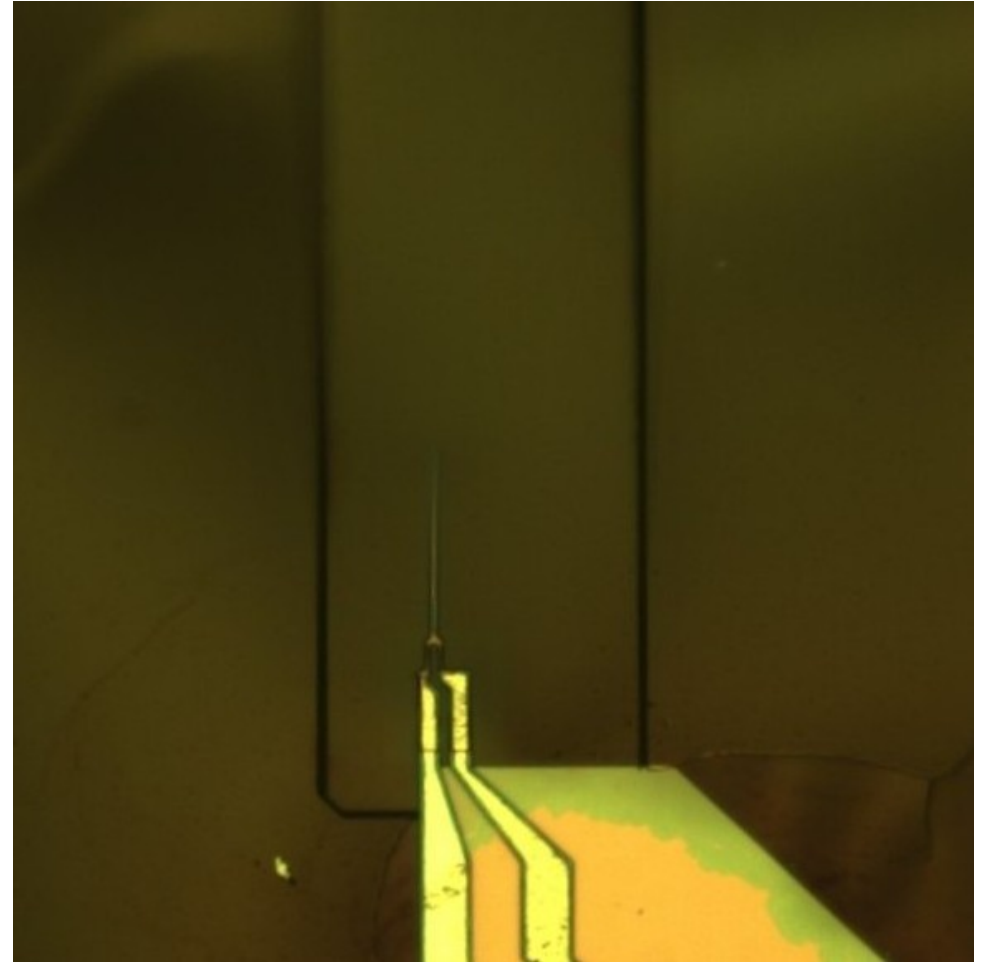


Recycled another image on the reticle
(steppers are the greatest)

Cracking and Cantilever Yield

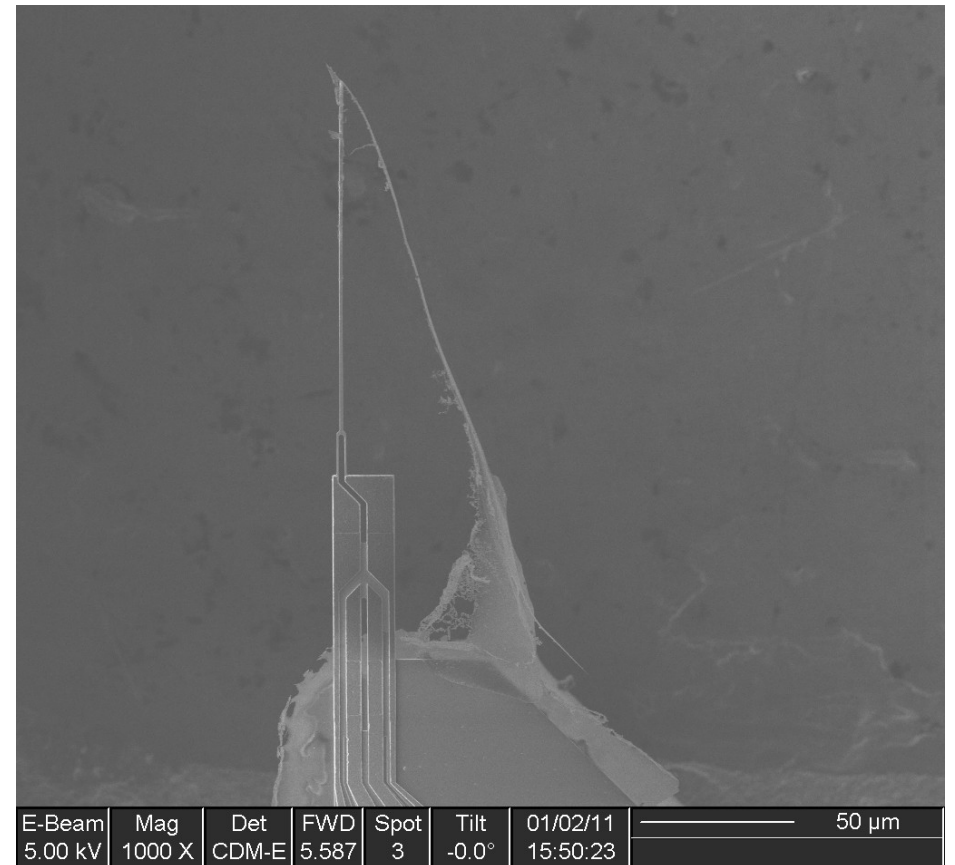


$30 \pm 15\%$ (10-50%)
(n = 8 wafers)



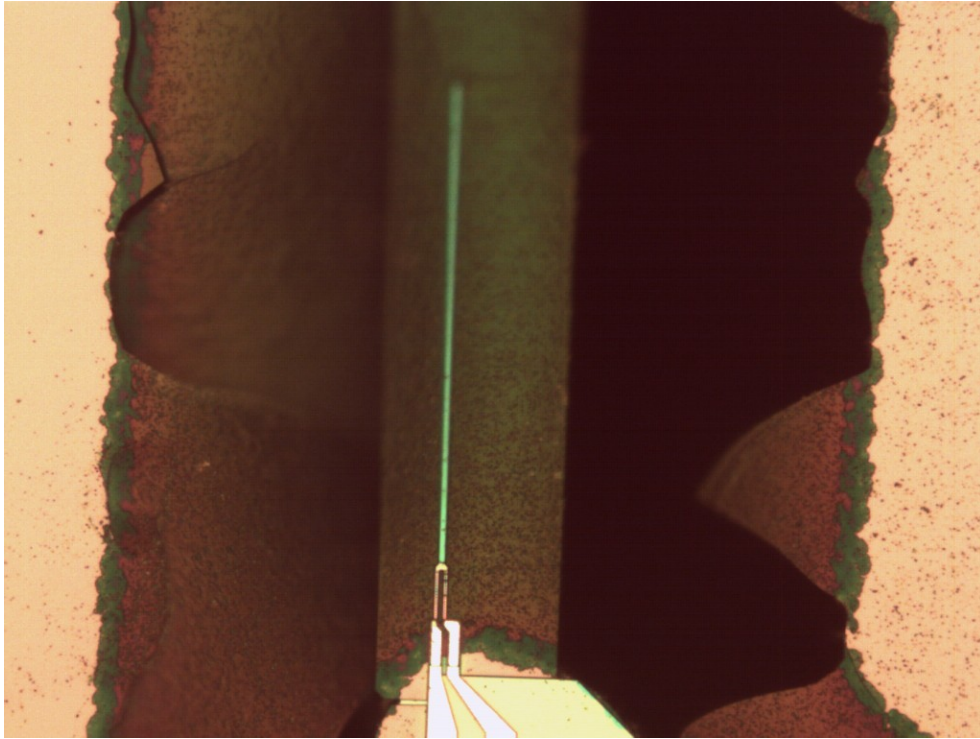
$70 \pm 17\%$ (51-91%)
(n = 4 wafers)

Polymer Goop

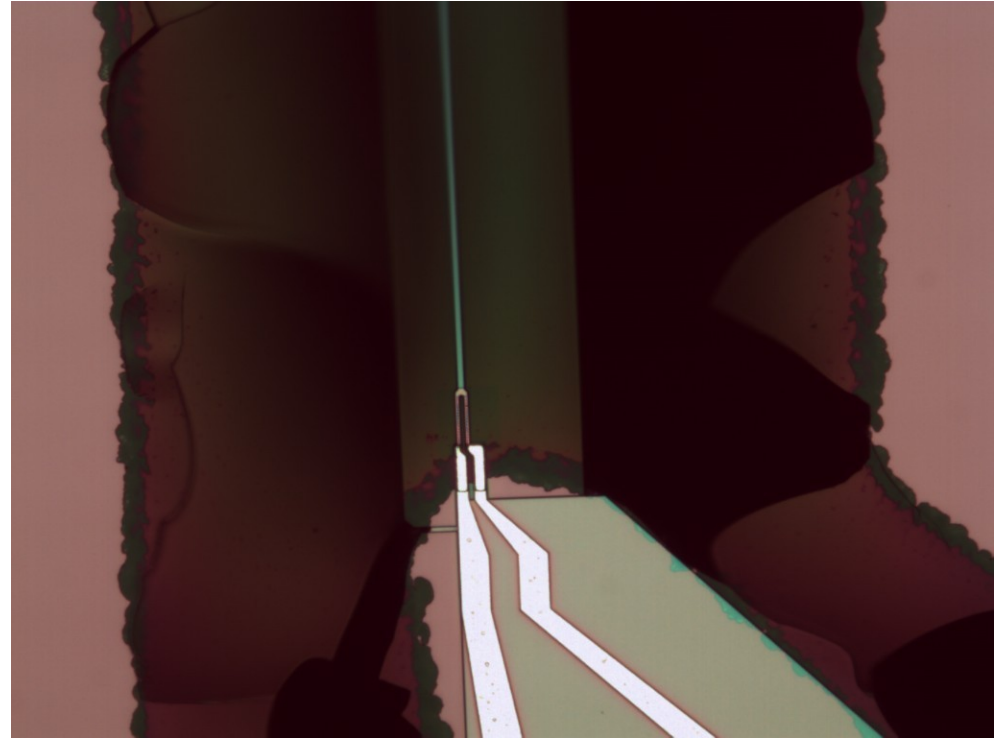


Polymers oxidize in oxygen plasma, right?

Polymer Goop

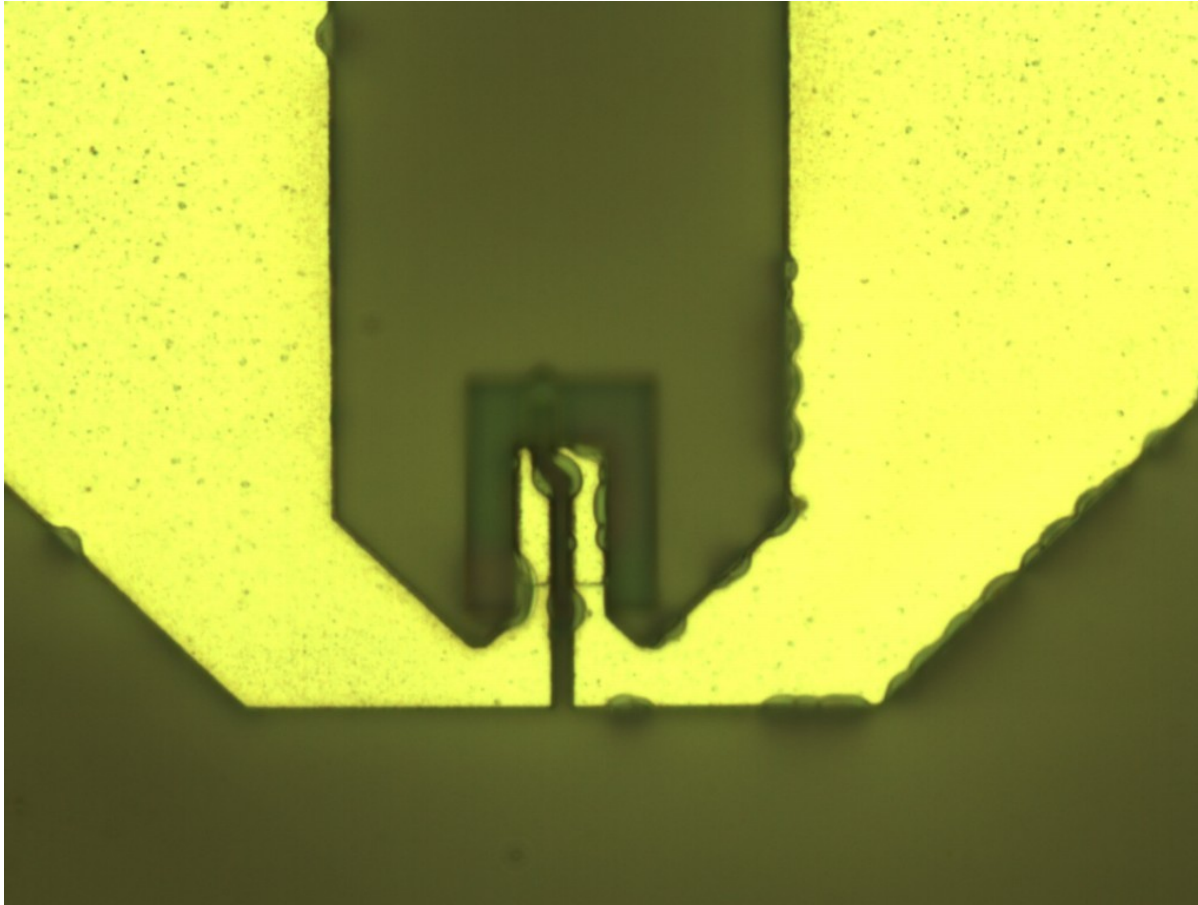


After 60min O₂ plasma
(apparently not)



After 2min O₂/CF₄/SF₆ plasma
(addition of fluorine allows
the fluorocarbons to oxidize)

Polymer Goop



Related: Coat everything in LTO before etching
(to prevent corrosion during hot water release
and for protection from the fluorine)

The End Result



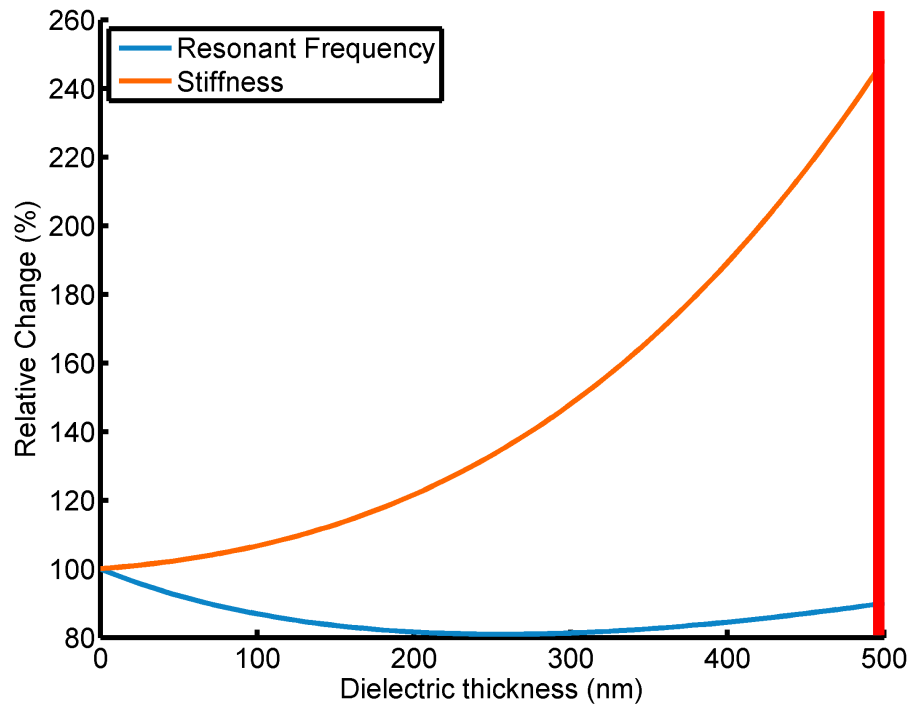
**Poly-on-insulator
Piezoelectric actuator**

Passivation

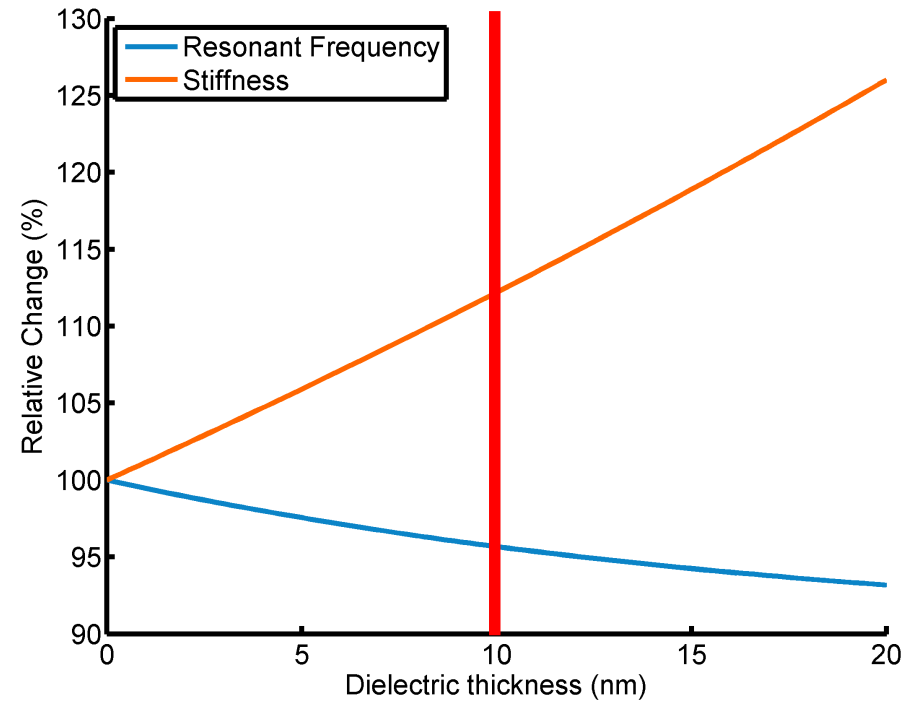
- Devices need to be insulated
 - Electrochemical corrosion
 - Shunt resistance
- Parylene
 - Somewhat conformal
 - >500nm thick to coat all exposed surfaces
 - Polymer → soft and squishy, water permeable
- Atomic layer deposition (ALD) metal oxides
 - Conformal and pinhole free for >4nm
 - Ceramic → hard, not very water permeable

Passivation

Parylene N



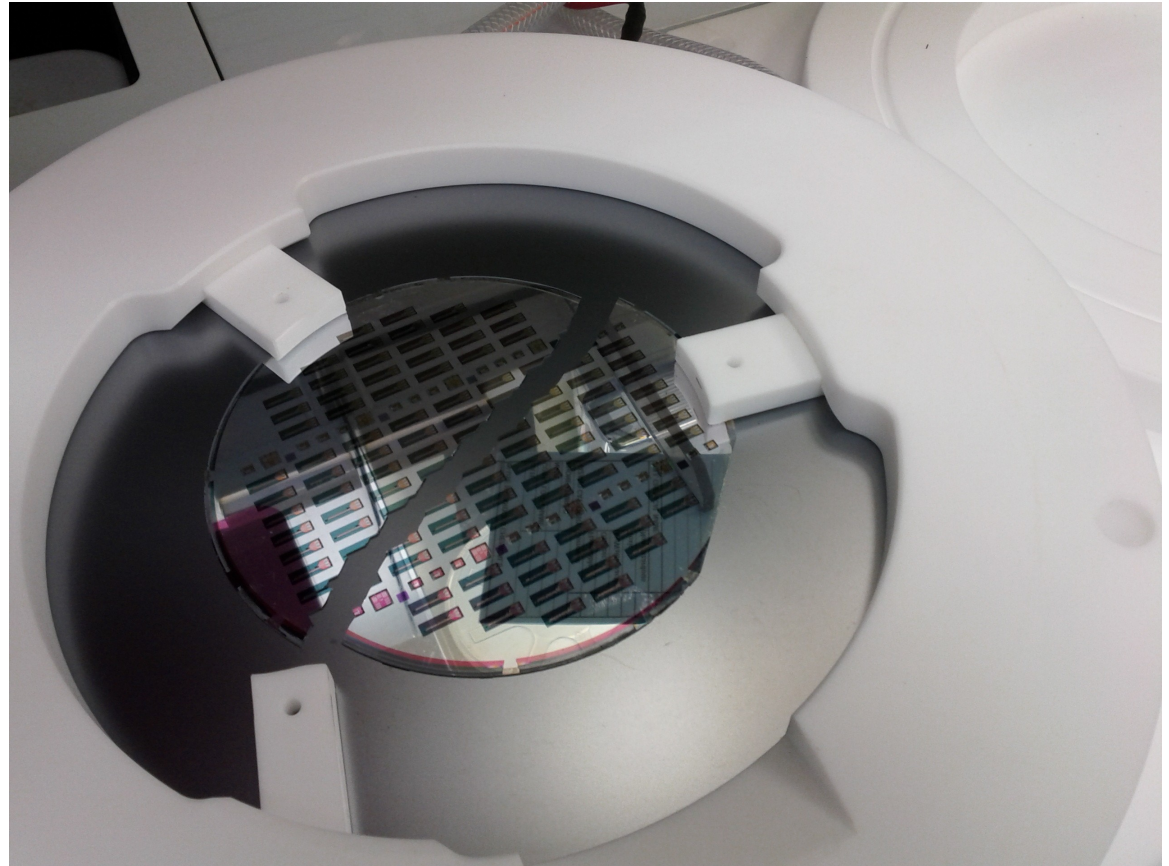
Hafnium oxide



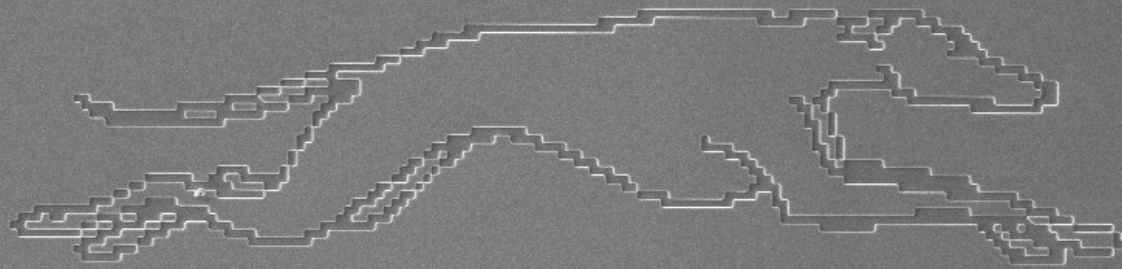
(Detailed ALD electrochemistry experiments are ongoing with Alex H.)

Conclusions

- Just finished releasing 8 wafers
 - 2 PE wafers done
 - ~3 good wafers
- Shipping the last batch to Michigan
 - 5 wafers today
 - 4 wafers Thurs



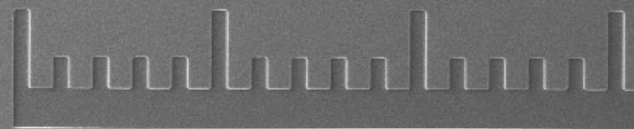
Questions?



10

20

100



E-Beam	Mag	Det	FWD	Spot	Tilt	01/11/11	 20 μm
5.00 kV	1.50 kX	CDM-E	5.730	3	-0.0°	11:36:44	